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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of

YANG, Nian, et al.

Serial No. 10/758,173

Filing Date: January 14, 2004

For: IMPROVING ELECTROSTATIC  
DISCHARGE PERFORMANCE OF A  
SILICON STRUCTURE AND  
EFFICIENT USE OF AREA WITH  
ELECTROSTATIC DISCHARGE  
PROTECTIVE DEVICE UNDER THE  
PAD APPROACH AND ADJUSTMENT  
OF VIA CONFIGURATION THERETO  
TO CONTROL DRAIN JUNCTION  
RESISTANCE

Examiner: WILSON, Scott R.

Art Unit: 2826

AMENDMENT AND RESPONSE TO OFFICE ACTION

Hon. Assistant Commissioner for Patents  
P.O. Box No. 1450  
Alexandria, Virginia 22313-1450

Sir:

In response to the Office Action mailed on January 21, 2005, please amend the above captioned patent application as follows and consider the following remarks.

There are no amendments to the specification in this responsive paper.

The Amendments to the Claims are reflected in the listing of the Claims, which begins on page 2 of this responsive paper.

The Remarks, with arguments, begin on page 8 of this responsive paper.